

### Amendments to the Specification

Please replace the paragraph beginning on on page 4, line 17 with the following amended paragraph:

As shown in FIG.2B, the defects 222 are filled using a mask shop to be estimated by chrome depositing, whereby contaminated areas 211 are formed on the substrate 21 in the vicinity of areas where the defects 222 are repaired. The light intensities  $Intensity_1$  of the contaminated areas 211, and the light intensities  $Intensity_2$  and  $Intensity_3$  of two sides of the contaminated areas 211 are measured using an Aerial Imaging Measurement System (AIMS), manufactured by Carl Zeiss, with 248-nanometer UV light source and processed with the MSM 100 software. The light intensity values of these areas are compared to nearby reference values to calculate the transmission of the repair in terms of a percent. Ratios  $Intensity_{bias}$  for each lines 221 are calculated according to the following equation.

$$Intensity_{bias} = \frac{Intensity_1 - (Intensity_2 + Intensity_3) / 2}{(Intensity_2 + Intensity_3) / 2}$$

Please replace the paragraph beginning on on page 6, line 1 with the following amended paragraph:

Therefore, the four ratios  $Intensity_{bias}$  are obtained for each group of the lines 321 with width of 0.6, 0.9 and  $1.2\mu m$ . A mean and  $3[\delta]\sigma$  value of the ratios  $Intensity_{bias}$  are also obtained for each group. The 3sigma value for each group is the number of ratios located within a range of  $\mu \pm 3\sigma$  where  $\sigma$  is the standard deviation of the normal

distribution. Accordingly, the repair accuracy of the mask shop is estimated. The number of the lines 321 is only for example and is usually more than 4 for a statistically effective estimation.

Please replace the paragraph beginning on on page 7, line 6 with the following amended paragraph:

Therefore, the twelve ratios  $\text{Intensity}_{\text{bias}}$  are obtained for each lines 421 respectively with width a of 0.6, 0.9 and  $1.2\mu\text{m}$  and width b of 0.3, 0.5, 0.7 and  $1.0\mu\text{m}$ . However, the number of the lines 421 with a certain width a and b is usually more than 1 (here for example) for a statistically effective estimation. In this case, a mean and  $3[\delta]\text{sigma}$  value of the ratios  $\text{Intensity}_{\text{bias}}$  are also obtained for each group of lines with a certain width a and b. Accordingly, the repair accuracy of the mask shop is estimated.

Please replace the paragraph beginning on on page 8, line 13 with the following amended paragraph:

In conclusion, in the present invention, by using the mask shop to repair the defects on the vertical and horizontal line with different widths and defect areas, and statistically calculating the means and  $3[\delta]\text{sigma}$  values of the ratios  $\text{Intensity}_{\text{bias}}$  defined in the invention, the repair accuracy of the mask shop is estimated. This provides a basis for engineers to determine a qualified mask shop.